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Substitute for form 1449A/B/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(Use as many sheets as necessary)</i>				Complete if Known	
				Application Number	10/689,820 - 4370
				Filing Date	October 21, 2003
				First Named Inventor	Karen K. Gleason et al.
				Art Unit	1762
				Examiner Name	Not Yet Assigned
				Attorney Docket Number	101328-179
Sheet	1	of	3		


U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No.	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code* (if known)			
EF	AA	4,599,243	07/08/1986	Sachdev et al.	
	AB	5,521,126	05/28/1996	Okamura et al.	
	AC	6,068,884	05/30/2000	Rose et al.	
	AD	6,090,724	07/18/2000	Shelton et al.	
	AE	6,107,357	08/22/2000	Hawker et al.	
	AF	6,214,746 B1	04/10/2001	Leung et al.	
	AG	6,258,735 B1	07/10/2001	Xia et al.	
	AH	6,313,045 B1	11/06/2001	Zhong et al.	
	AI	6,319,858 B1	11/20/2001	Lee et al.	
	AJ	6,358,863 B1	03/19/2002	Desu et al.	
	AK	6,391,932 B1	05/21/2002	Gore et al.	
	AL	6,420,441 B1	07/16/2002	Allen et al.	
	AM	6,455,443 B1	09/24/2002	Eckert et al.	
	AN	6,495,479 B1	12/17/2002	Wu et al.	
	AO	6,541,367 B1	04/01/2003	Mandal	
	AP	6,541,865 B2	04/01/2003	Hawker et al.	
	AQ	2001/0004479 A1	06/21/2001	Cheung et al.	
	AR	2003/0006477 A1	01/09/2003	Gallahger et al.	
	AS	2003/0001239 A1	01/02/2003	Gallahger et al.	
EF	AT	2002/0137359 A1	09/26/2002	Grill et al.	

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No.	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ^o
		Country-Number				
EF	BA	EP 1 321 976 A2	06/25/2003	Canon Sales Co., Inc.		
EF	BB	EP 1 148 539 A2	10/24/2001	Applied Materials, Inc.		
EF	BC	EP 1 195 451 A1	04/10/2002	Applied Materials, Inc.		
EF	BD	WO 03/005429 A1	01/16/2003	Postech Foundation		

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OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
EF	CA	Baklanov, M.R. et al. "Comparative Study of Porous SOG Films With Different Non-Destructive Instrumentation," IEEE pp. 189-191, (2001);	
	CB	Barklanov, M.R. "Determination of Pore Size Distribution In Thin Films By Ellipsometric Porosimetry" J. Vac. Sci. Technol. B., Vol. 18, No. 3, pp. 1385-13981, (2000);	
	CC	Baklanov, M.R., Mogilnikov, K.P., "Non-Destructive Characterisation of Porous Low-K Dielectric Films," Microelectronic Engineering, Vol. 64, pp. 335-349, (2002);	
	CD	Chen, J.Y. et al. "Microstructure and Mechanical Properties of Surfactant Templated Nanoporous Silica Thin Films" Effect of Methylsilylation," Journal of The Electrochemical Society, Vol. 150, No. 6, pp. F123-F127 (2003);	
	CE	Grill, A. and Neumayer, D. A. "Structure of Low Dielectric Constant To Extreme Low Dielectric Constant SiCOH Films: Fourier Transform Infrared Spectroscopy Characterization," Journal of Applied Physics, Vol. 94, No. 10, pp. 6697-6707 (2003);	
	CF	Grill, A. and Patel, V. "Ultralow-k Dielectrics Prepared By Plasma-Enhanced Chemical Vapor Deposition," Applied Physics Letters, Vol. 79, No. 6, pp. 803-805 (2001);	
	CG	Grill, A. "Plasma Enhanced Chemical Vapor Deposited SiCOH Dielectrics: From Low-k To Extreme Low-k Interconnect Materials," Journal of Applied Physics, Vol. 93, No. 3, pp. 1785-1790 (2003);	
	CH	Grill, A et al. "Characteristics of Low-k and Ultralow-k PECVD Deposited SiCOH Films," Mat. Res. Soc. Symp. Proc., Vol. 716, pp. B12.3.1-B12.3.6 (2002);	
	CI	Grill, A. et al. "Porosity In Plasma Enhanced Chemical Vapor Deposited SiCOH Dielectrics: A Comparative Study," Journal of Applied Physics", Vol. 94, No. 5, pp. 3427-3435, (2003);	
	CJ	Grill, A. and Patel, V. "Low Dielectric Constant Films Prepared By Plasma-Enhanced Chemical Vapor Deposition From Tetramethylsilane," Journal of Applied Physics, Vol. 85, No. 6 pp. 3314-3318 (1999);	
	CK	Hedrick, J. L. et al. "Templating Nanoporosity In Thin-Film Dielectric Insulators," Adv. Mater. Vol. 10, No. 13 pp. 1049-1053 (1998);	
	CL	Park, S.H. and Xia, Y. "Macroporous Membranes With Highly Ordered And Three-Dimensionally Interconnected Spherical Pores," Advanced Materials, Vol. 10, No. 13, pp. 1045-1053 (1998);	
	CM	Peters, L. "Low-K Dielectrics: Will Spin-On or CVD Prevail?," Semiconductor international, pp. 108-124, (2000);	
	CN	Peters, L. "Removing Barriers To Low-K Dielectric Adoption," Semiconductor International 53-62, (2002);	
	CO	Sanchez, M.I. et al. "Nanofoam Porosity By Infrared Spectroscopy," Journal of Polymer Science: Part B: Polymer Physics, Vol. 33, pp. 253-257 (1995);	
	CP	Sanchez, M.I. et al. "Nanofoam Porosity Measured By Infrared Spectroscopy And Refractive Index," Mat. Res. Soc. Symp. Proc., Vol. 431, pp. 475-480, (1996);	
	CQ	Vrtis, R.N. et al. "Plasma Enhanced Chemical Vapor Deposition of Porous Organosilicate Glass ILD Films With k < 2.4.," Mat. Res. Soc. Symp. Proc., Vol. 766, pp. E7.4.1-E7.4.6, (2003);	
	CR	Wu, Q. and Geason, K.K. "Plasma-Enhanced Chemical Vapor Deposition of Low-k Dielectric Films Using Methylsilane, Dimethylsilane, and Trimethylsilane Precursors," J. Vac. Sci. Technol., Vol. A 21, No. 2, pp. 388-393 (2003);	
BC	CS	Yang, S. et al. "Nanoporous Ultralow Dielectric Constant Organosilicates Templated By Triblock Copolymers," Chem. Mater., Vol. 14, pp. 369-374 (2002);	

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EF	CT	Yim, J-H. et al. "The Preparation and Characterization of Small Mesopores In Siloxane-Based Materials That Use Cyclodextrins as Templates," Adv. Funct. Mater., Vol. 13, No. 5, pp. 382-386 (2003);	
EF	CU	Ye, Y-H. et al. "Large-Scale Ordered Macroporous SiO ₂ Thin Films by a Template-Directed Method," Applied Physics Letters, Vol. 81, No. 4, pp. 616-618, (2002);	
EF	CV	Zhang, P. et al. "Theory of Metastable Group-IV Alloys Formed From CVD Precursors," Physical Review B, Vol. 64, pp. 235201-1- 235201-10 (2001).	
Examiner Signature			Date Considered 3/29/04

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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